

### **REMARKS**

Claims 5 and 13 remain pending in the application. The Examiner is respectfully requested to reconsider and withdraw the rejections in view of the amendments and remarks contained herein.

### **REJECTION UNDER 35 U.S.C. § 103**

Claims 5 and 13 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Baude (U.S. Pat. Pub. No. 2003/0150384) in view of Hirayanagi et al (U.S. Pat. No. 6,171,736). These rejections are respectfully traversed.

Claims 5 and 13 call for a deposition mask including silicon and being provided with an electrode arranged interdigitally in a mask pattern portion. According to the claimed configuration, the substrate which is the subject of deposition is prevented from warping. In contrast, none of the prior art discloses this feature. In fact, Baude teaches a chamber where a mask is not loosened.

In view of the foregoing, reconsideration and withdrawal of these rejections are respectfully requested.

### **CONCLUSION**

It is believed that all of the stated grounds of rejection have been properly traversed, accommodated, or rendered moot. Applicant therefore respectfully requests that the Examiner reconsider and withdraw all presently outstanding rejections. It is believed that a full and complete response has been made to the outstanding Office Action and the present application is in condition for allowance. Thus, prompt and

favorable consideration of this amendment is respectfully requested. If the Examiner believes that personal communication will expedite prosecution of this application, the Examiner is invited to telephone the undersigned at (248) 641-1600.

Respectfully submitted,

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By: 

G. Gregory Schivley  
Reg. No. 27,382  
Bryant E. Wade  
Reg. No. 40,344

HARNESS, DICKEY & PIERCE, P.L.C.  
P.O. Box 828  
Bloomfield Hills, Michigan 48303  
(248) 641-1600

[GGS/BEW/cmh]